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Depositor: Karen Cing-Mars

(Signature & date)

Karen Cing-Mars 8/12/03

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of _____: August 12, 2003
Hendrik F. Hamann et al. : Group Art Unit:
Serial No. 10/604,487 : Examiner:
Filed: 07/25/2003 : International Business Machines Corporation
2070 Route 52
Hopewell Junction, NY 12533

TITLE: SYSTEMS AND METHODS OF ALTERING A VERY SMALL SURFACE AREA

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

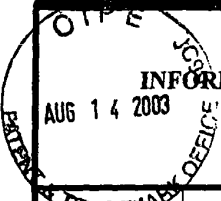
Pursuant to the duty of disclosure set forth in 37 C.F.R. 1.56, and further pursuant to the provisions of 37 C.F.R. 1.97 and 1.98, applicants hereby respectfully submit copies of the prior patents and publications as listed on Form PTO-1449, attached hereto.

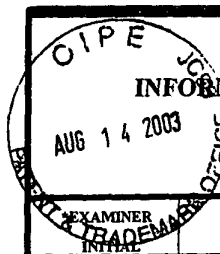
In citing these documents, no representation is made nor intended as to the pertinency or non-pertinency of the art, that better art than that listed is not available, or that other art is not applicable.

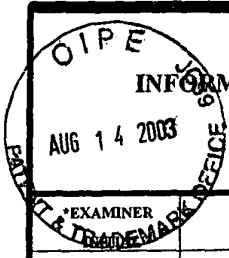
Respectfully submitted,
Hendrik F. Hamann et al.

BY

Steven Capella
Steven Capella, Attorney
Registration No. 33,086
Telephone No. 845-894-3669

 <p>INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)</p>		Docket Number (Optional) FIS920020166US1	Application Number 10/604,487
		Applicant(s) Hendrik F. Hamann et al.	
		Filing Date 07/25/2003	Group Art Unit
<p>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</p>			
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	A Nanoplotter with Both Parallel and Serial Writing Capabilities, Seunghun Hong and Chad A. Mirkin, Science Magazine, Vol. 288, June 9, 2000		
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	The NSOM-100 A Multifunctional Near-Field Optical Scanned Probe Confocal Microscope, www.nanonics.co.il		
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EXAMINER		DATE CONSIDERED	
<p>*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>			

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		Dip-Pen Nanolithography on Semiconductor Surfaces, Albena Ivanisevic et al., J. Am. Chem. Soc. 2001, 123, 7887-7889.	
		Multiple Ink Nanolithography: Toward a Multiple-Pen Nano-Plotter, Seunghun Hong et al., Science Magazine, Vol. 286, 10/15/1999.	
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		Research Shows Potential of Nanojets for Smaller Circuitry & Injecting Games, Science Daily Magazine, 08/31/2000.	
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		1998 SRC Annual Review, Near-Field Optics for Metrology and Lithography, Research ID 438, Robert Grober, Dept. of Applied Physics, Yale University.			
		Maskless Lithography Using Scanning Probes, Kathryn Sara Wilder, GL report No. 5670, Edward L. Ginzton Lab., Stanford University, August 1999.			
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		Technology of Proximal Probe Lithography, Christie R.K. Marrian, Naval Research Laboratory, SPIE Institutes, Volume IS 10, 1993.			
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